

METHOD FOR GAP FILLING BETWEEN METAL-METAL LINES

A method for gap filling between metal-metal lines is provided so that a first dielectric layer forms on a surface and side wall of a plurality of metal lines thereon which is called partially HDP deposition. Then, a portion of the first dielectric layer is removed by a high-density plasma with Ar/O₂ to sputter so that a portion of side wall of metal lines is exposed. Afterwards, a second dielectric layer is formed on the first dielectric layer by a method of high density plasma oxide deposition so that the metal lines are completely covered.